OPTICAL PROPERTIES OF CO-EVAPORATED THIN FILMS OF BINARY Bi₂O₃-Te O₂ AND Bi₂O₃-V₂O₅ SYSTEMS

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Abstract

Thin films of binary $\mathrm{Bi_2O_3}$ - $\mathrm{TeO_2}$ and $\mathrm{Bi_2O_3}$ - $\mathrm{V_2O_5}$ systems were prepared by the thermal co-evaporation technique in a vacuum at room temperature. The optical absorption edge of these systems are studied in the wavelength of 200-800 nm using a PERKIN-ELMER uv/vis spectrophotometer. It is found that the value of n=3/2 in the Davis-Mott equation is best fitted for the fundamental absorption edge for these materials. It is also found that the optical energy gap ($\mathrm{E_{opt}}$) for the $\mathrm{Bi_2O_3}$ - $\mathrm{V_2O_5}$ system lies between 0.65 and 3.5 eV. and for the $\mathrm{Bi_2O_3}$ - $\mathrm{TeO_2}$ system between 0.95 and 3.25 eV. depending on the film composition. The exponential behaviour of the absorption coefficient with photon energy for the systems under investigation are verified as suggested by Urbach.

Introduction

The analysis of optical spectra over a wide range of photon energy has been one of the most productive tools for understanding and developing the theory of electronic structure in crystalline and amorphous solids. For the amorphous materials in the high absorption region, which is associated with interband transition, Tauc [1] and Davis-Mott [2] independently derived an expression relating the absorption coefficient $\alpha(\omega)$ to the photon energy ($\hbar\omega$) as,

$$a(\omega) = A \frac{(\hbar_{\omega} - E_{opt})^n}{\hbar \omega}$$
 (1)

where E_{opt} is the optical energy gap and n is a number

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which characterizes the optical absorption processes. Its values for different kinds of transitions are as follows:

n= 1/2: direct-allowed transition [3]

n= 1: non-metalic materials [4]

n= 3/2: direct-forbidden transition [5,6,7]

n= 2: indirect-allowed transition [8]

n= 3: indirect-forbidden transition [3]

A in Equation (1) is a constant and is given by,

$$A = \frac{4\pi \ G_0}{ncE_{e\,l}} \tag{2}$$

where c is the speed of light, n is the refractive index of the material, G is the extrapolated dc. conductivity at T=0 K and $E_{\rm cl}$ is the extent of the band tailing.

The absorption edge in many disordered materials

follows the Urbach rule [9] given by:

$$a_{(\infty)} \propto Exp\left(\frac{\hbar\omega}{\Delta E}\right)$$
 (3)

where ($\hbar\omega$) is the photon energy and ΔE is the width of the tail of the localized states in the band gap.

Experimental Procedure

Sample Preparation

Thin films of Bi_2O_3 - TeO_2 and Bi_2O_3 - V_2O_5 binary systems with different composition were coated on cleaned Corning 7059 glass substrate using thermally co-evaporation technique at room temperature under a pressure of $p \cong 4 \times 10^{-6}$ torr.

Samples specification and the condition of preparation are given in Tables 1 and 2. Tungsten boats were found to be most suitable for the evaporation since boats made of other materials react with the evaporants, as was confirmed by XPS. The film thickness and rate of deposition were monitored using a quarts crystal monitor unit (Intellometrics model IL-150).

The absorption coefficient for the samples listed in

Tables 1 and 2 was calculated from the following equation,

$$\alpha_{(\omega)} = \frac{1}{d} \ln \frac{I_0}{I_t} \tag{4}$$

where $\alpha(\omega)$ is the absorption coefficient, I_0 and I_1 are the intensities of incident and transmitted light, respectively, and d is the thickness of the film.

Optical Data Measurement

We have investigated Bismuth oxide in thin film form to determine,

- a) the position and shape of absorption edge.
- b) the value of n, in Equation (1) and therefore the kind of transition in these materials.
 - c) the optical energy gap, E_{opt}, and
- d) the effects of increasing the concentration of Vnadium oxide and Tellerrium oxide on absorption edge and the value of E_{xx}.

On the basis of our earlier experiments related to the other binary systems containing V_2O_5 and CeO_2 we found that as the concentration of V_2O_5 in the V_2O_5 -CeO₂ system decreases the absorption edge becomes sharper

Table 1. Optical absorption data for Bi₂O₃-V₂O₅ system with different composition

Sample No.	Composition Bi ₂ O ₃ -Te-O ₂	Thickness nm.	E _{opt.} eV.	Pressure Torr	Temperature K
2010	88%-12% 63%-37%	360	3.5	2.10 ⁻⁶	305
2011	56%-44%	345	2.55	2.10-6	300
2013	42%-58%	340	1.72	2.5.10-6	304
2014	28%-72%	330	1.23	3.10-6	306
2015	15%-85%	355	0.65	1.10-6	308
100.a	100%-00%	560	3.60	5.10-6	312

Table 2. Optical absorption data for Bi₂O₃-V₂O₅ system with different composition

Sample No.	Composition Bi ₂ O ₃ -Te-O ₂	Thickness nm.	E _{opt.} eV.	Pressure Torr	Temperature K
1050	23%-77%	440	0.98	2 .10-6	304
1006	39%-61%	410	1.2	2.5 .10-6	305
1007	56%-44%	480	1.35	2 .10-6	302
1008	72%-28%	475	1.75	3 .10-6	299
1009	86%-14%	450	3.25	4.5 .10-6	300

and the optical energy gap increases from 2.1 eV. for pure V_2O_5 to 3.2 eV. for the system containing 17% V_2O_6 -83% CeO₂ [8].

In this work we wish to find out the effect of V_2O_5 and TeO_2 concentration on the optical properties of a binary system containing Bi_2O_3 . The recorded absorption spectra for all the samples listed in Tables 1 and 2 are shown in Figure 1 for the Bi_2O_3 - V_2O_5 and in Figure 2 for the Bi_2O_3 - TeO_2 system. The absorption spectra for pure Bi_2O_3 is shown in Figure 3. To determine the value of n, in Equation (1) for the systems under investigation, the variations of $(\alpha \hbar \omega)^{1/n}$ vs. photon energy were plotted for different values of n. It was found that n=3/2 gives the best linear dependence in the high absorption region for both systems, indicating that the kind of transition in these systems is a direct-forbidden transition as it was reported for other systems containing transition metal oxides [5].

Sample specifications and optical absorption data for the systems under investigation are given in Tables 1 and 2. Figures 4 and 5 represent the variation of (αhω)^{2/3} with photon energy for these systems with different composition. The extrapolation of the linear part of these curves to the energy axis at the value of (chm)2/5=0 gives the values of E_{opt}. The variation of E_{opt} with Bi₂O₃ content for both Bi,O,-V,O, and Bi,O,-TeO, systems are shown in Figure 6 and 7, respectively. From these figures one can see that for both systems the effect of increasing the Bi₂O₄ content is an increase in the optical energy gap which could arise as a result of a reduction in the higher valency state of transition metal ion in the system. To achieve a more reliable conclusion the electron spin resonance (E.S.R) experiment is recommended to evaluate the concentration of different valency states of Vanadium [13]. (V^{+5}, V^{+4}, V^{+3}) , as well as, the concentration of the non-bridging oxygen ions in the

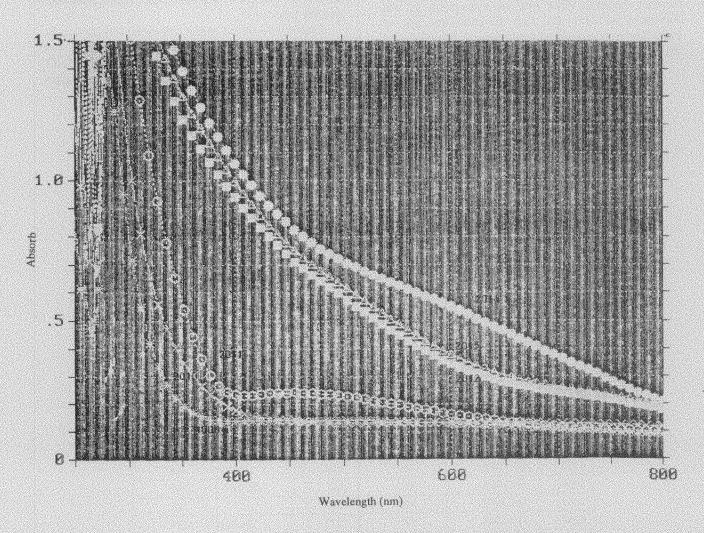


Figure 1. UV. Spectra of Bi₂O₃-TeO₂ system as listed in Table 1.

samples under study.

It is well established that in many crystalline and amorphous semiconductors the absorption coefficient $\alpha(\omega)$ depends exponentially on photon energy $\alpha(\omega)$. This behaviour was suggested by Urbuch [9] for the first time in the form of Equation 2. The origin of this kind of dependence is not clearly known.

Tauc [10] suggested that the exponential behaviour arises from the electron transition between localized states where the density of localized states is exponentially dependent on photon energy (Band tais). Another suggestion is based on the presence of a strong internal electric field due to structural disorder [11]. Mott and Davis have rejected the Tauc suggestion because the slope of the exponential absorption edge is much the same in a variety of materials.

Variation of Ln(-a) with photon energy (fiw) for both systems are shown in Figure 8 and 9. These figures show

that the absorption coefficient, in terms of photon energy for both Bi₂O₃-TeO₂ and Bi₂O₃-V₂O₅ systems follows the Urbach exponential rule.

1. If the films behave as quasiintrinsic semiconductors, the Fermi energy will be located in the middle of the band gap and the electrical energy gap $E_{\rm el}$ would be twice the activation energy and equal to the optical gap ($E_{\rm el}=E_{\rm opt}$). But if the values of the electrical activation energy is much less than the optical energy gap it would be clear that the electrical activation process is certainly not across a band gap but rather between bands and trapping centres.

Conclusion

The results of optical absorption measurements for the systems under study is summerized as follows;

The absorption spectra observed in amorphous Bi₂O₃-V₂O₄ and Bi₂O₄-TeO₂ thin films in the wavelength region

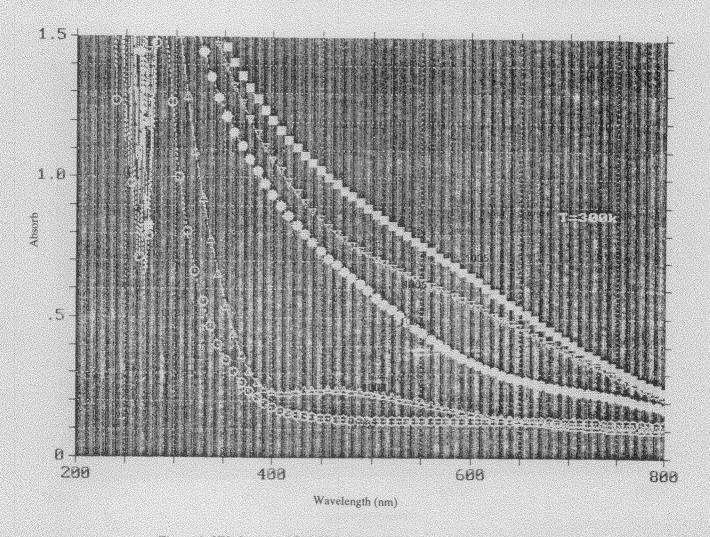


Figure 2. UV. Spectra of BiO₃V₂O₅ Bi₂O₅-V₂O₅ system as listed in Table 1.

of 200-800 nm have similar structures as in many binary oxide systems.

The fitted value of n= 3/2 indicates that the transition in these materials is a K-conserving transition (direct-forbidden transition, without phonon envolvement) which shows that the electron wave function in the valence band near K= 0 is not much different from those in crystal.

For both systems the optical absorption edge becomes sharper as the content of Bi₂O₃ increases and for a film with a high concentration of Bi₂O₃ the absorption edge is similar to that of crystalline structure.

The optical energy gap for the Bi_2O_3 - V_2O_5 system ranges from 0.65 to 3.5 eV, depending on composition and increases with Bi_2O_3 concentration. For the Bi_2O_3 - TeO_2 system the optical energy gap varies between 0.95 and 3.25 eV, and increases with the content of Bi_2O_3 in the system.

Absorption coefficients in both systems follows the Urbach exponential dependent on the photon energy indicating the existence of localized states at the band tails arising from the lack of long range order in these systems.

To give a more qualitative description of the transition mechanism and extent of the band tailing an E.S.R measurement is recommended to evaluate the concentration of different valency states in these systems.

Electrical measurements such as a.c and d.c conductivity could be useful in evaluating the extent of band tailing and the concentration of localized states in the tailes region, as well as, trapping centres.

To evaluate the strength of the bonding, specially the concentration of non-bridging V-O and Te-O bonding and the strength of the possible Bi-Te bonding, IR and X-ray spectroscopy measurements are also recommended.

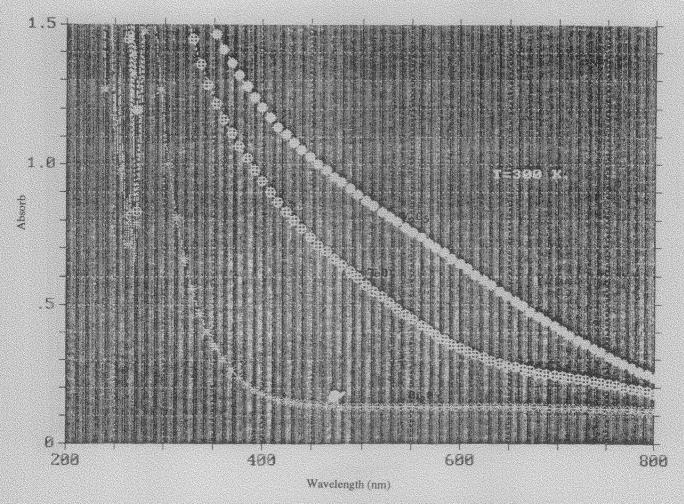


Figure 3. UV. Spectra of pure TeO₂, V₂O₅, and Bi₂O₃ samples

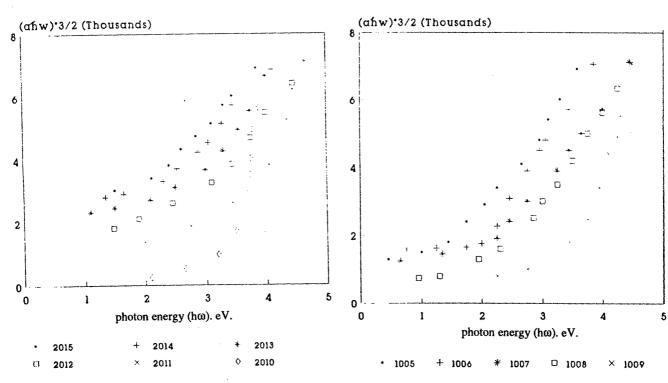


Figure 4. Variation of $(\alpha h\omega)^{*3/2}$ vs. (hw) for $Bi_2O_3\text{-}V_2O_5$ system

Figure 5. Variation of $(\alpha h\omega)^{*3/2}$ vs. $(\hbar\omega)$ for Bi_2O_3 -TeO₂ system

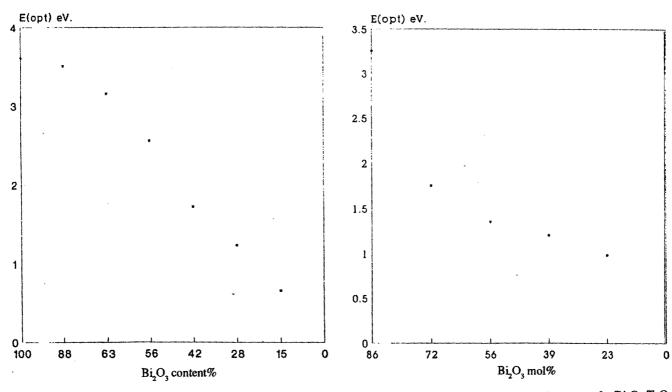
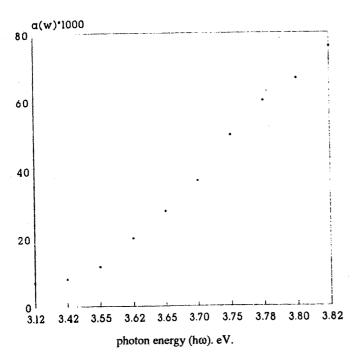


Figure 6. Variation of E(opt) vs. Bi_2O_3 content for Bi_2O_3 - V_2O_5 system

Figure 7. Variation of E(opt) vs. Bi₂O₃ content for Bi₂O₃-TeO₂ binary system



Sample no 2010

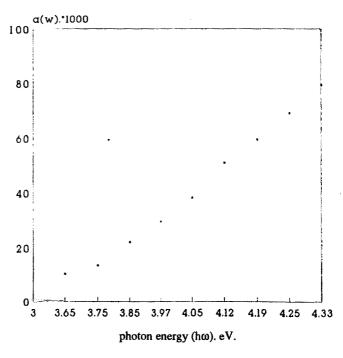
Figure 8. Variation of $\propto(\omega)$ vs. photon energy $(h\omega)$ for the sample no 2010

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Sample no 1008

Figure 9. Variation of $\alpha(\omega)$ vs. photon energy for the sample no 1008

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